









The physical implementation of MAPS



Context

- Importance of hierarchical design
- Large design challenges
- Emerging needs
- Conclusion

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- Goal: Less material means better physics
- How is it achieved?
  - □ Lower power consumption allows for air cooling
  - On chip data transfer allows no flex
  - Bent Si wafers allow stable mechanical structure
  - Proposal: Wafer-scale stitched particle detectors



Dummy silicon model



- Stitching: technique that allows some parts of the reticule to be repeated across a wafer to create a unique circuit
- MOSS (Monolithic Stitched Sensor) prototype is a proof-of-concept of stitched MAPS
  - □ 1.4 by 26 cm wide
  - □ 1.67 million pixels
  - 736.3 million transistors
- How to achieved the design of such sensors?









# 14 mm 1 2 3 4 5 6 7 8 9 1000 25890 25.9 cm

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### Implementing DRD7 - frederic.morel@iphc.cnrs.fr



## There are 4 aspects to master: Hierarchy, Granularity, Timing, and Power

□ The Learning Map @ C4Pi





- Large and complex designs need a hierarchy to keep the submission on schedule
- 2 well known approaches:
  - Bottom-up
    - The design of each block is "independent"
    - All the constraints are seen at the top, at the end of the flow
  - □ Top-down
    - The top constraints of the system are pushed down to the blocks
    - Need a dedicated flow
    - Works at early stage with partially defined blocks
- Hierarchical flow helps the designers with
  - Partitioning
    - Push floorplan constraints into blocks
  - Time budgeting
    - The timing constraints are allocated between top and partitions
- Hierarchy could be nested



- Digital flow is based on abstraction of cells
  - □ Liberty file: timing and power model
  - □ Abstract: physical view
  - □ Power Grid View (PGV): extracted power network
- Granularity is related to the size of the blocks in the hierarchy
  - □ Which is the best: Pixel, column, sub-array or matrix level?
  - □ Need to be in phase with functional verifications
- Runtime of the flow and verification accuracy are correlated to the granularity
  - □ Need to be flexible during the flow (place and route stages vs signoff stage)
- Generating the abstraction for coarse-grained blocks could be difficult
  - On a huge block it could take days or did not converge at all
  - □ It is much easier for the blocks that come from Innovus than for those that come from Virtuoso



- Need to model the timing of digital hierarchical blocks at high level to reduce the runtime
- 2 types of modelling: ETM (Extracted Timing Model) and ILM (Interface Logic Model)
  - □ ETM generates a liberty file of the block
  - □ ILM works on a reduced netlist
- ETM can be long and difficult to generate and has many drawbacks
- ILM is more efficient but still has some limitations





- A full flat signoff analysis is required to avoid missing failed paths with hierarchical timing
  - Not all corners are used during place and route steps
  - Problems with interactions between blocks and top
- Knowledge of the tools is essential for success in a reasonable time
  - □ Flatten the design using advanced capability of Tempus
  - Distributed timing verification
    - Careful tuning between corners and remote hosts is needed to get the best performance
  - Use hierarchical ECO flow to fix remaining fall paths
- Similar techniques are available for power verifications

MIMOSIS2 full flat timing analysis Reticule size chip in 0.18 μm		Local hierarchical 1 CPU	Local no physical 16 CPU	Local physical 16 CPU	Distributed physical 4 hosts with 4 CPU
	Total Time (h)	0.3	4	4.2	4.5
	CPU Time (h)	0.3	32.5	32.75	52
	Peak Memory (GB)	20	110	120	47 for each host







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## Convergence between digital and analogue world

- Signal Integrity glitch analysis for analogue nets
  - □ Estimation of the injection peak on an analogue net and make the corrections on violated nets
  - □ High-precision simulations (spectre)
- Dynamic Rail Analysis for On-Chip Voltage Regulators with Voltus
  - □ Simulate a reduced circuit with spectre
  - Inject the simulated voltage waveforms into Voltus rail solver



## To further improve the quality of design: new tools are needed

- Need to use new tools to ensure good yield of stitched sensors
  - DRC clean and traditional filling is not sufficient (recommended rules and smart filling)
  - Yield dominated by a few hotspots
- Calibre DFM provides access to a set of analyses
  - □ For some analyses, foundry rules are mandatory
  - □ For some analyses, some basic self check could be performed to identify the weakest points



## Figure 11-1. Manufacturing Defects



#### ry 🔴 Cell Summary 🔴 Window Summary 🖨 Drill Down Avg Quality poly.OPEN 0.94347 poly.SHORT 0.950443 6921.78 netal1 OPEN 0.860505 19483 2 0.925032 1 88042 16701.3 Window Summary 0 954673 6330.96 0.894509 14734.3 Browse Hierarchy Errors 0.968548 4393.00 962319 5263.07 08551\_deta .80 Highlight Flat Errors m Extent (0.0 Histogram Hierarchy Cel Enable Autoran ap Flat Erro 0.959156 0.918312 Critical Area - 0.043 0.87746 Critical Area: 0.09 ritical Area 0.15 0.836623 Critical\_Area : 0.525 Critical\_Area : 0.738

## Another particles detector

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- Design methodologies are essential to produce high quality sensors on time
- The sensor is part of an overall system → Do we need to go for digital twins?
- Relationships with foundries and EDA vendors are critical
- Potential bottleneck in computing infrastructure